Fabrication of Photonic LPCVD Silicon-Nitride Waveguides

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Overview

- Project Goals
- Photonics Overview
- Photomask Design
- Process Flow
- Results
- Acknowledgements

Project Goals

Fabricate TE mode Nitride Waveguides using the tools available in the RIT SMFL Cleanroom

Amorphous silicon waveguides have already been made

Demonstrate loopback waveguides with ring resonators

Qualify Nitride Waveguides against similar designs

◆Lay the groundwork for research to come:

Get test results showing similar transmission as Eigenmode Solution Simulation of 450nm thick and 1000nm wide



Photonics Overview

Photonics is the study of transmission and detection of light

Instead of wires, we have waveguides

Integrated photonic circuits uses photons and electricity to transmit data

Integrated photonic circuits branch optical physics and microelectronics



Why Photonics is Needed

Electrical interconnects limited in voltage and frequency, driving power consumption up

Hard to scale due to bandwidth being limited by size

Photonics allows for high bandwidth and low power consumption

Data transmission is much faster





Mask Design

Design Variations:

- Loopback Waveguide
 - Varied Grating Coupler Taper
 - Varied Grating Coupler Pitch
 - Varied Waveguide Length
- Ring Resonator Waveguide
 - Varied Grating Coupler Taper
 - Varied Grating Coupler Pitch
 - Varied Resonator Gap



Mask Design

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1000nm Width Loopback Waveguides



Varied Grating Parameters: Pitch: 700nm – 1500nm Taper: 100µm – 1000µm



Test Head Setup



[1] Sanjna Lakshminarayanamurthy, 2017

500nm Width Resonator Waveguides



Varied Grating Parameters: Pitch: 700nm – 1500nm Taper: 100µm – 1000µm



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Process Flow

Nitride Critical Dimensions of: 500nm, 1000nm, and 1500nm



Focus Exposure Matrix

New film stack being used requires different dose exposure

New Photoresist being used in the lab: MiR 701

Typical exposure dose: 275mJ/cm²

FEM Exposure variation from 175mJ/cm² to 375mJ/cm²

Best exposure dose: 185mJ/cm²

Resolved 0.375µm lines and spaces



Photoresist Problems

First photoresist exposure showed poor resolution

- Small photoresist lines not sticking to surface
- Used PRS2000 to chemically strip photoresist and attempted again
- Concluded: Nitride left surface rough

Chemical strip and rinse did surface preparation that allowed good adhesion





Fabrication Results



Fabricated Loopback Waveguide with 1.5µm width, 1µm coupler pitch, and 400µm coupler taper



Close up of Grating Coupler showing 0.5µm line and space resolution

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Fabrication Results



Fabricated Resonator Waveguide with 0.5µm width, 1µm coupler pitch, and 300µm coupler taper



Close up of resonator gap showing 0.3µm space between waveguide and ring

Simulation Results

Test Head Angle Variation to optimize transmission through Grating Coupler

✤ Varied from 20 degrees to 30 degrees with best result of 24 degrees



Simulation Results

Grating Coupler Pitch Variation to optimize transmission

Varied from 700nm to 1500nm with best result of 1300nm



What's Next

Next Step: *Physical testing of the fabricated waveguides*

- Improve process to get smaller features
- Project focused more on the fabrication than simulation and optimization
- Simulations for each waveguide to compare the "ideal" to actual
- More simulations to redesign mask and get better transmission and lower loss
- Create a tunable thermo-optic waveguides or CMOS photonic structures

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